

**INFORMATION
DISCLOSURE
STATEMENT**

Atty. Docket No.: 150.00650102

Serial No.: 09/603,132

Applicant(s): Brian A. Vaartstra et al.

Filing Date: June 23, 2000

Group: 2825

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	SubClass	Filing Date If Appropriate
EL	4,907,052	03/06/90	Takada et al.			
EL	5,168,332	12/92	Kunishima et al.			
EL	5,270,241	12/14/93	Dennison et al.			
EL	5,362,632	11/08/94	Mathews			
EL	5,372,849	12/13/94	McCormick et al.			
EL	5,392,189	02/21/95	Fazan et al.			
EL	5,491,365	02/13/96	Chin et al.			
EL	5,510,651	04/23/96	Maniar et al.			
EL	5,520,992	05/28/96	Douglas et al.			
EL	5,555,486	09/10/96	Kington et al.			
EL	5,561,307	10/01/96	Mihara et al.			
EL	5,566,045	10/15/96	Summerfelt et al.			
EL	5,581,436	12/03/96	Summerfelt et al.			
EL	5,612,574	03/18/97	Summerfelt et al.			
EL	5,618,746	04/08/97	Hwang			
EL	5,637,527	06/10/97	Baek			
EL	5,679,980	10/21/97	Summerfelt			

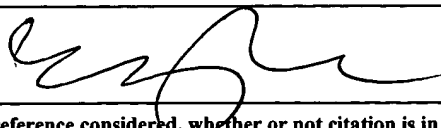
FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	SubClass	Translation	
						Yes	No
EL	0 856 879	08/05/98	EPO				

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

EL	H. D. Bhatt et al., "Novel high temperature multilayer electrode-barrier structure for high density ferroelectric memories," Appl. Phys. Letter, 71, 719-721 (1997).
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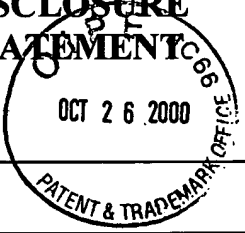
EXAMINER

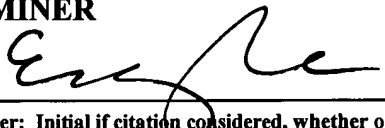


Date Considered

3/27/01

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EL		Green et al., "Chemical Vapor Deposition of Ruthenium and Ruthenium Dioxide Films," <u>J. Electrochem. Soc.</u> , <u>132</u> , 2677-2685 (1985).
EL		T. Kawahara et al. "(Ba, Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <u>Jpn. J. Appl. Phys.</u> , <u>35</u> 4880-4885 (1996).
EL		Liao et al., "Characterization of RuO ₂ thin films deposited on Si by metal-organic chemical vapor deposition," <u>Thin Solid Films</u> , <u>287</u> , 74-79 (1996).
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